

L Number	Hits	Search Text	DB	Time stamp
2	7754	134/1.1,2,22.1,22.14,22.18,22.19,34,30,902.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/30 09:24
3	7868	134/1.1,2,22.1,22.14,22.18,22.19,34,30,902.ccls. or 438/905.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/30 09:24
4	965	(134/1.1,2,22.1,22.14,22.18,22.19,34,30,902.ccls. or 438/905.ccls.) and @pd>20030227	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/30 09:25
5	9	((134/1.1,2,22.1,22.14,22.18,22.19,34,30,902.ccls. or 438/905.ccls.) and @pd>20030227) and ("CF3CF=CF2" or C3F6 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/30 09:28
6	61	mitsushi near2 itano	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/30 09:28
7	2	(mitsushi near2 itano) and ("CF3CF=CF2" or C3F6 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/30 09:28
-	4	(chamber adj clean\$3) with (CF3CF=CF2 or (hexafluoropropylene or hexafluoropropene))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 10:57
-	30397420	CF3CF=CF2 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 12:19
-	74448	(CF3CF=CF2 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)) and CVD and (etch\$3 or clean\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 11:31
-	21274	((CF3CF=CF2 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)) and CVD and (etch\$3 or clean\$3)) and (CVD with (etch\$3 or clean\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 11:54
-	2484	((CF3CF=CF2 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)) and CVD and (etch\$3 or clean\$3)) and (CVD with (etch\$3 or clean\$3) with chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 12:20
-	1924	(((CF3CF=CF2 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)) and CVD and (etch\$3 or clean\$3)) and (CVD with (etch\$3 or clean\$3) with chamber)) and plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 11:32
-	1	(CF3CF=CF2 or (hexafluoropropylene or hexafluoropropene)) with (CVD with (etch\$3 or clean\$3) with chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 11:41

	0	((CF3CF=CF2 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)) and CVD and (etch\$3 or clean\$3)) and (((8/159   8/158   8/149.3   8/142).CCLS.) and steam\$3) and (tumb\$3 or rotary or rotat\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 11:54
	4	((CF3CF=CF2 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)) and CVD and (etch\$3 or clean\$3)) and ("4581101"   "5198634"   "5281302"   "5376234"   "5417826"   "5445712"   "5679215"   "5882424"   "5897377"   "5902403"   "5925611"   "5928963").PN.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 11:54
16697	16697	"CF3CF=CF2" or C3F6 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 12:20
	15	("CF3CF=CF2" or C3F6 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)) and (CVD with (etch\$3 or clean\$3) with chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 15:33
	73	("CF3CF=CF2" or C3F6 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)) and 134/.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 12:29
	146	("CF3CF=CF2" or C3F6 or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene)) and (CVD and (etch\$3 or clean\$3) and chamber) and plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 12:46
	3	"CF <sub>3</sub> CF <sub>2</sub> CF <sub>3</sub> CF <sub>2</sub> "	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 12:46
7466	7466	((deposition or CVD) with (etch\$3 or clean\$3) with chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 15:22
	92	(((deposition or CVD) with (etch\$3 or clean\$3) with chamber) and ("CF3CF=CF2" or C2F4 or C3H6 or C4H8) or (tetrafluoroethylene or tetrafluoroethene or perfluoroethylene or perfluoroethene) or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene) or (octafluorobutylene or octafluorobutene or perfluorobutylene or perfluorobutene))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 15:55
	6	(((deposition or CVD) with (etch\$3 or clean\$3) with chamber) and (cleaning adj gas with ("CF3CF=CF2" or C2F4 or C3H6 or C4H8) or (tetrafluoroethylene or tetrafluoroethene or perfluoroethylene or perfluoroethene) or (hexafluoropropylene or hexafluoropropene or perfluoropropylene or perfluoropropene) or (octafluorobutylene or octafluorobutene or perfluorobutylene or perfluorobutene)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 15:27
2484	2484	(((deposition or CVD) with (etch\$3 or clean\$3) with chamber) and (CVD with (etch\$3 or clean\$3) with chamber))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/26 15:33